

Nano-Tribological Printing: A novel additive manufacturing method for nanostructures

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Additive Manufacturing (AM) has enabled rapid prototyping and manufacture of components with highly complex shapes

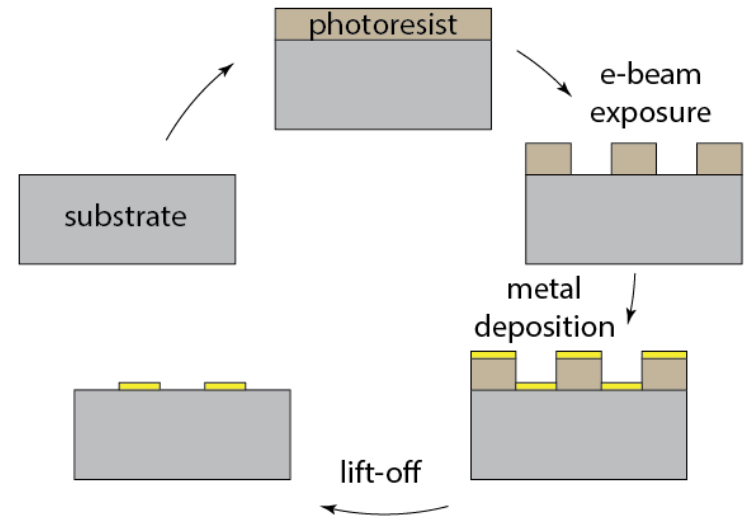


Though initially restricted to soft polymers, more recent AM techniques are capable of manufacturing metallic and ceramic components

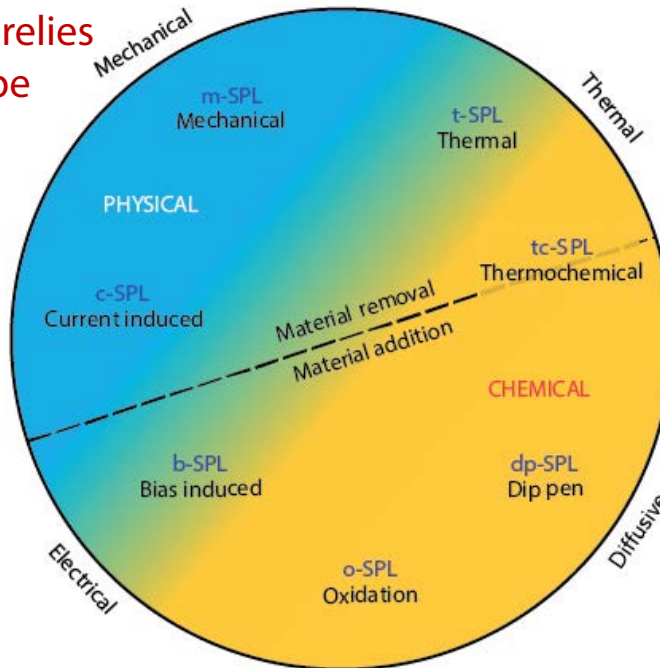


Traditional nanoscale patterning techniques include electron-beam lithography, nano-imprint lithography and molecular assembly

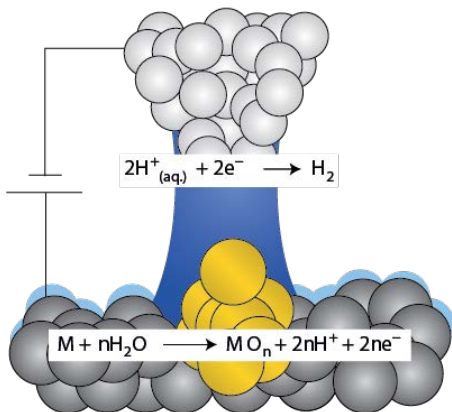
Most nanolithography techniques involve multi-step processes



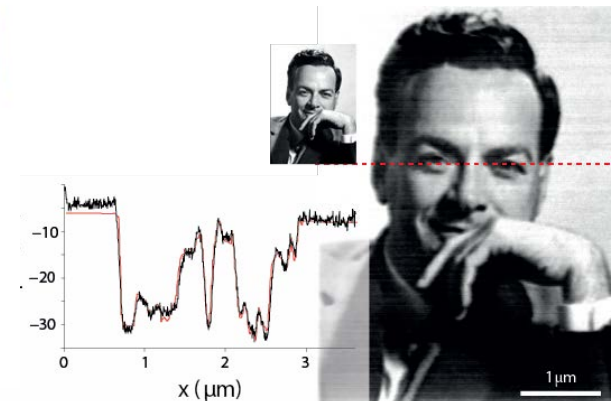
Scanning Probe Lithography (SPL) is a direct-write technique and relies on conventional Scanning Probe Microscopes

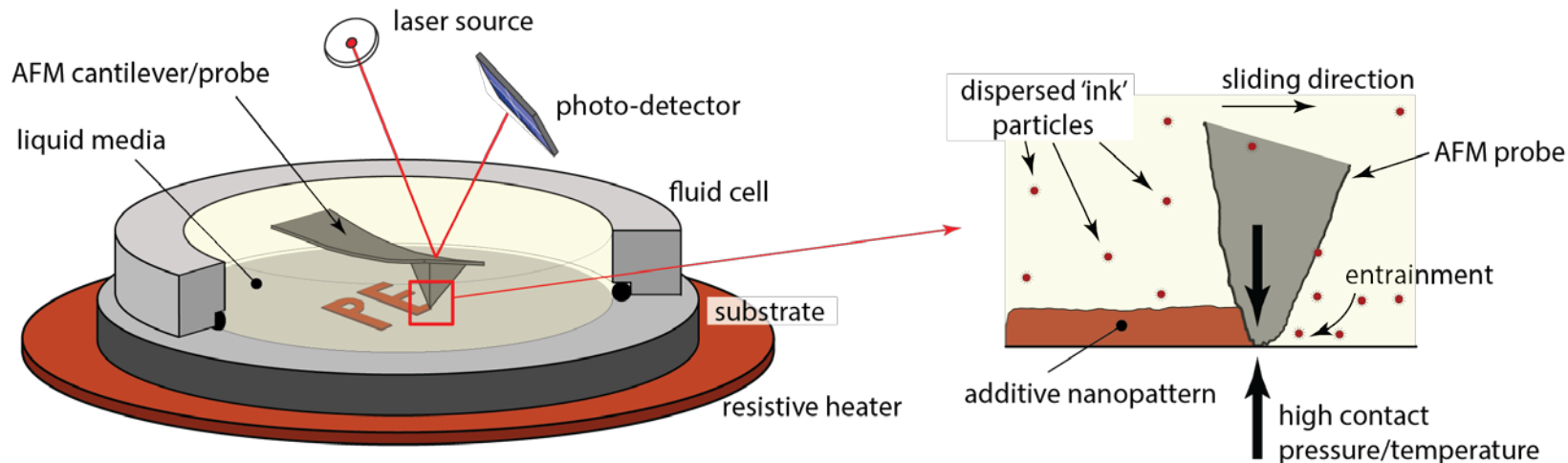


o-SPL: Material addition

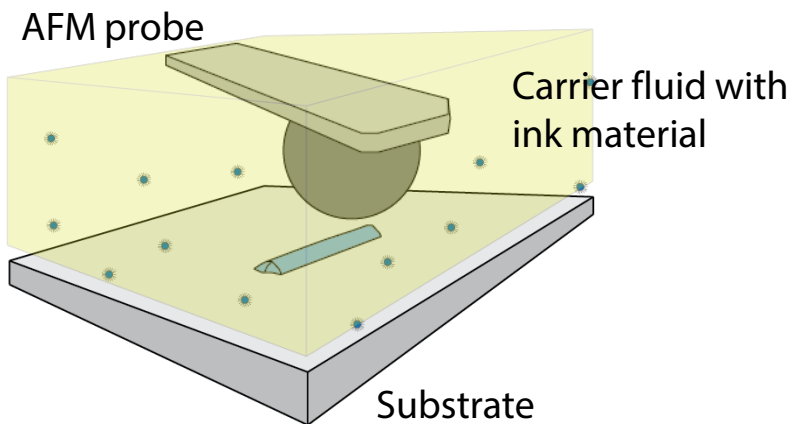


t-SPL: Material removal

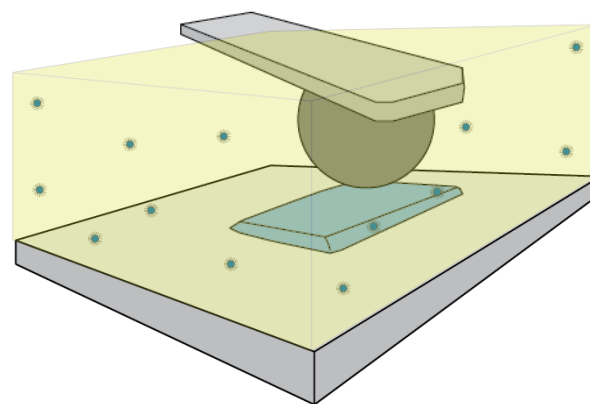




In Nano-Tribological Printing, patterning occurs due to *in-situ* confinement and stress-induced coagulation of ink material



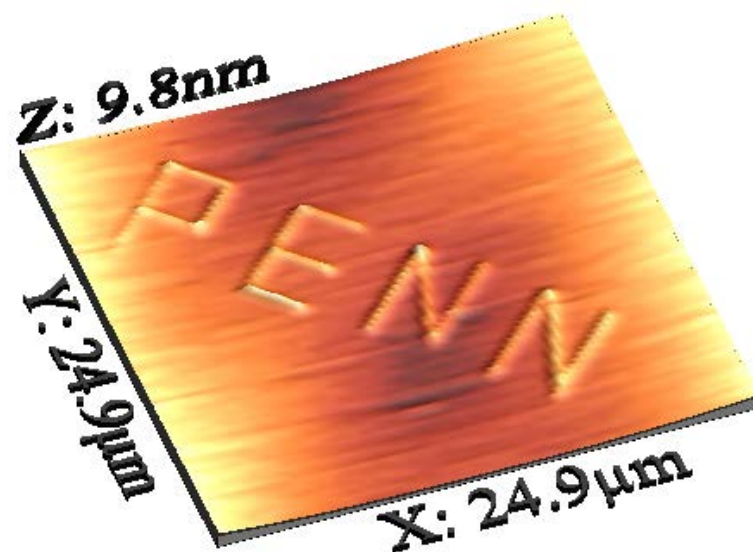
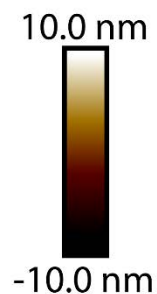
Tribological stresses induce patterning

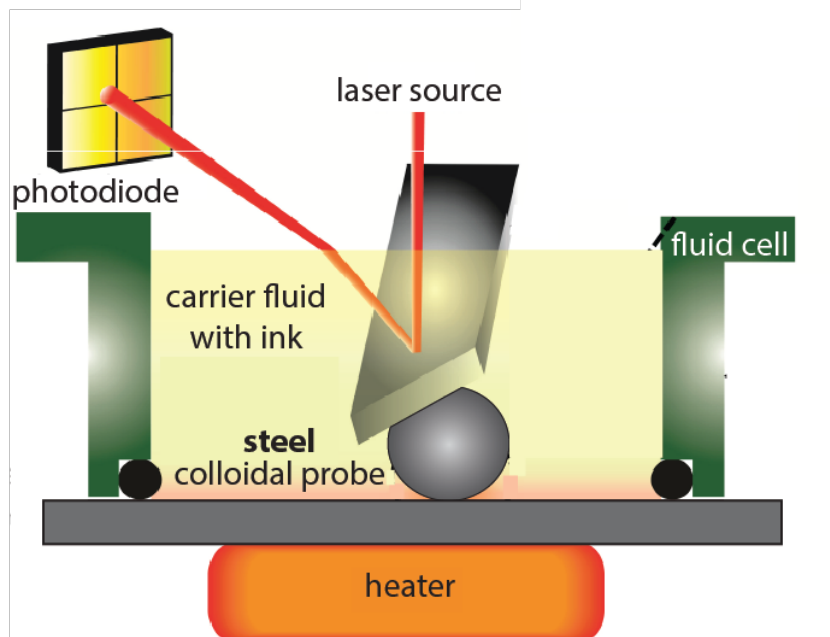


Variations in tip motion can be used for writing complex patterns



Programmed AFM-tip motion can be used for creating complex patterns

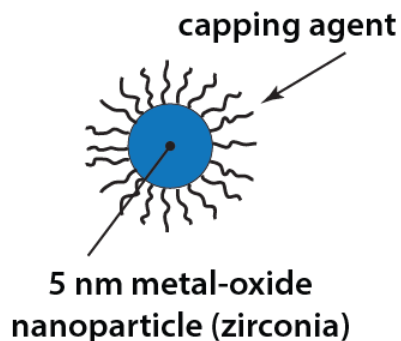
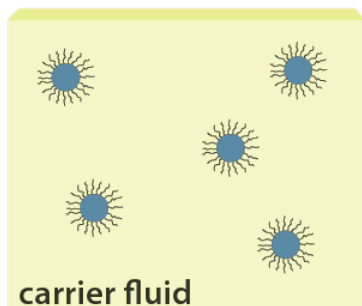




Fluid-cell Atomic Force Microscopy

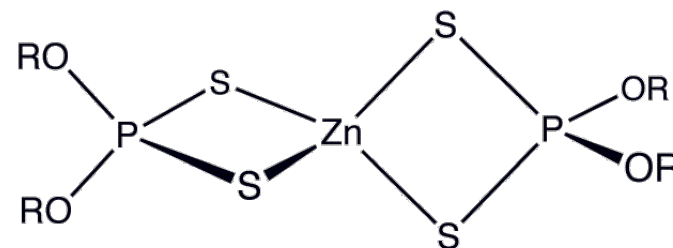
Nanoparticle patterning performed with steel colloids on different substrates (steel results reported here) in an AFM fluid cell.

Nanoparticle patterns were created at room temperature



Zirconia printing at room temperature

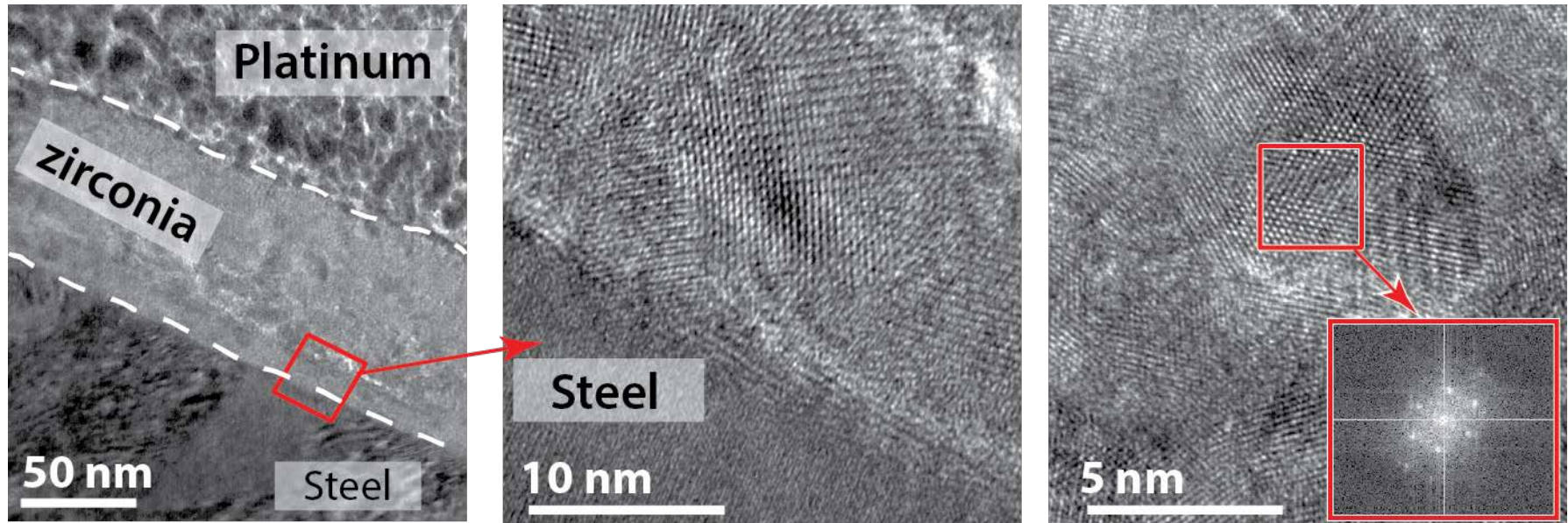
Nanoparticles as patterning ink



(R = alkyl)

Zinc Dialkyldithiophosphates (ZDDP) at high temperature

Molecular species as patterning ink

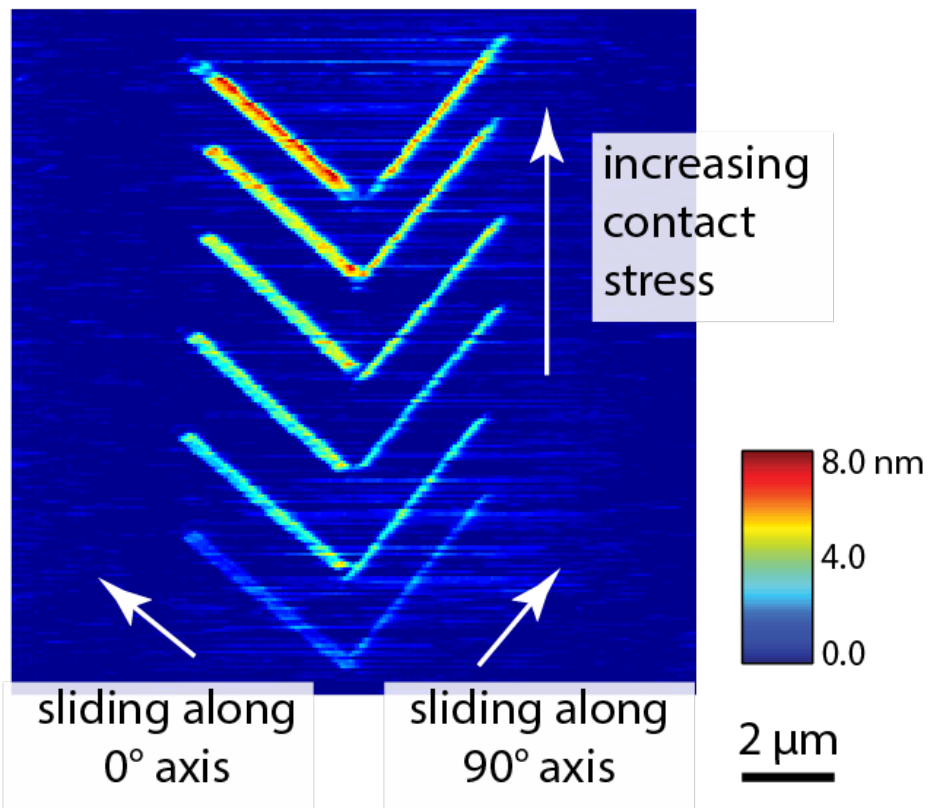


Tribological stress results in strong bonding between nanocrystals and a highly dense microstructure

Measured mechanical properties of zirconia patterns approach values reported for bulk zirconia

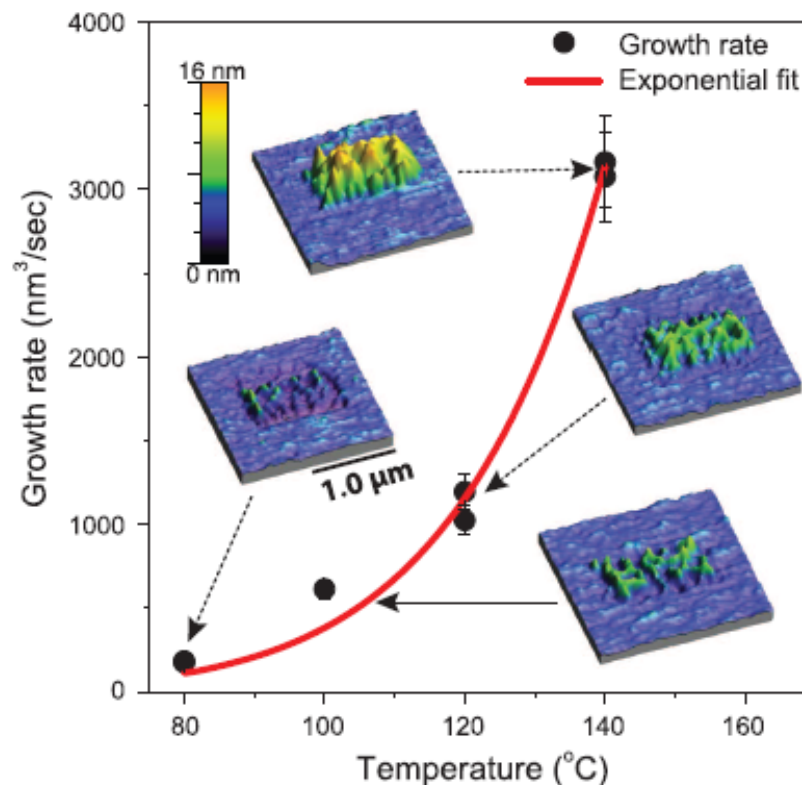
Samples	E (GPa)	H (GPa)
Bulk zirconia ⁽¹⁾	215-266	9.2
Nanoscale pattern	151.7 ± 5	7.3 ± 0.7

[1] J.F. Shackelford et al., Ceramic and Glass Materials: Structure, Properties and Processing, 2008



Pattern width changes with scan angle due to probe asymmetry

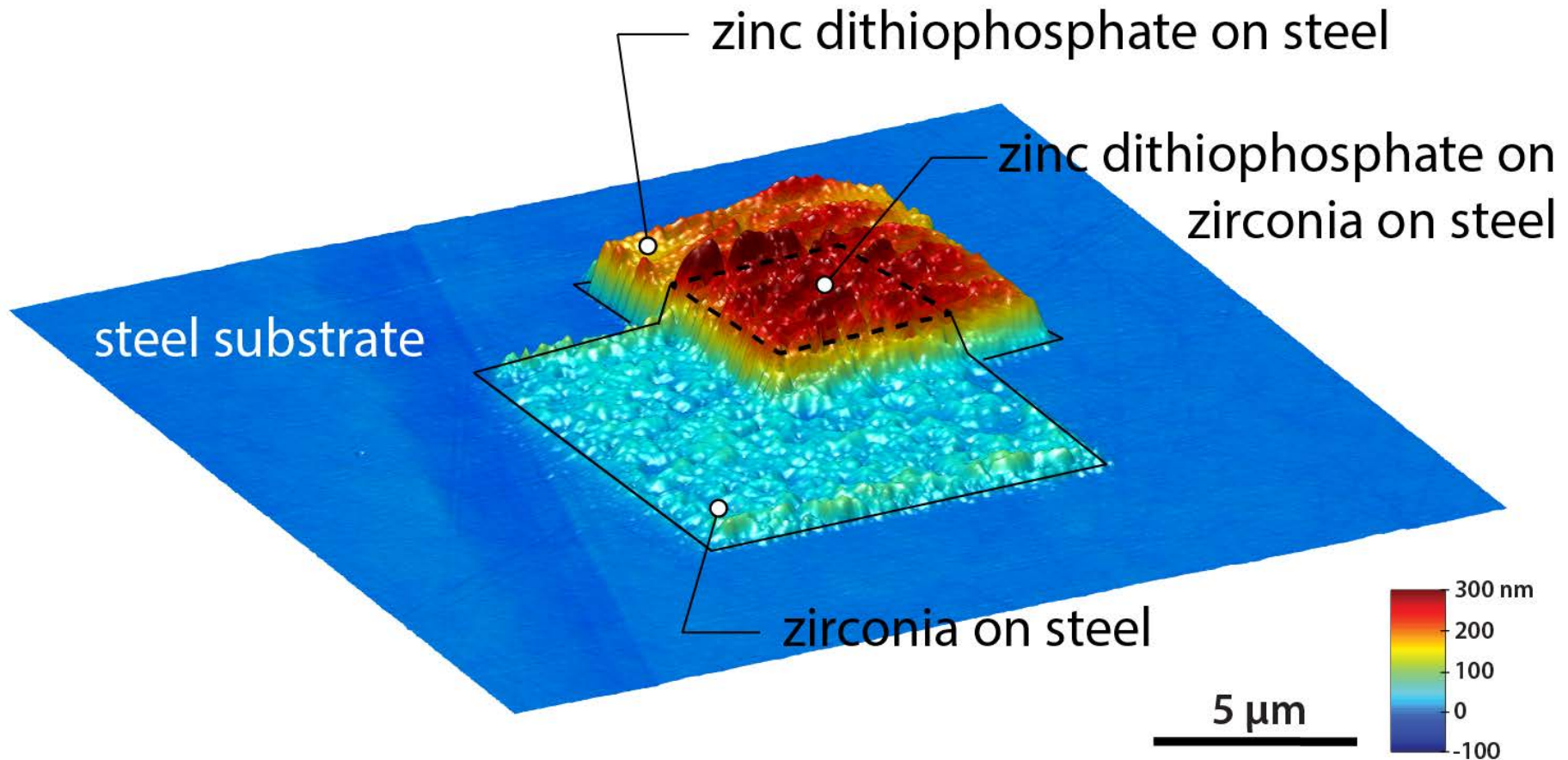
Pattern thickness varies with contact pressure



Patterning rate and pattern thickness can also be accelerated with temperature¹

ZDDP growth rate increases exponentially with temperature

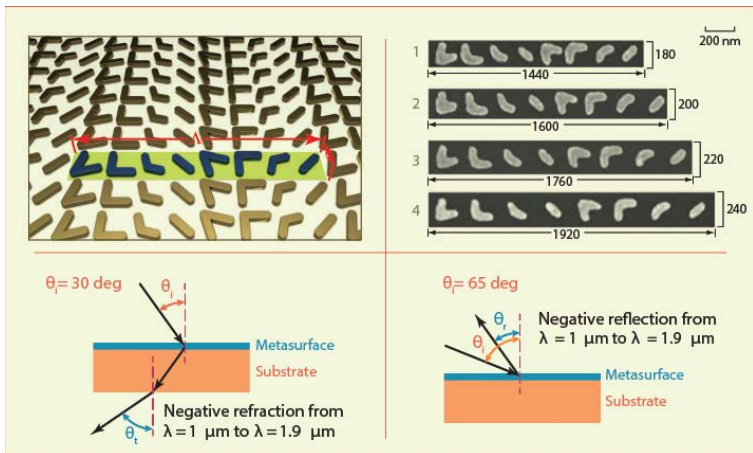
[1] N.N. Gosvami *et al.*, *Science* (2015)



Using multiple ink materials, layered nanostructures can also be generated

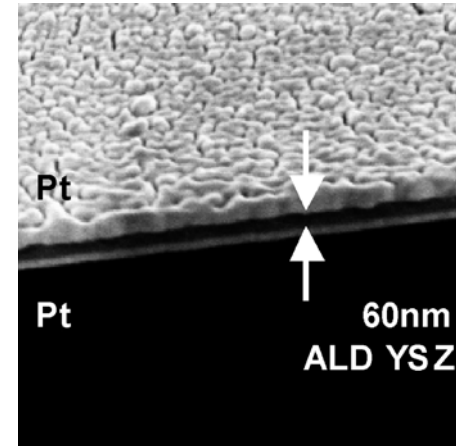
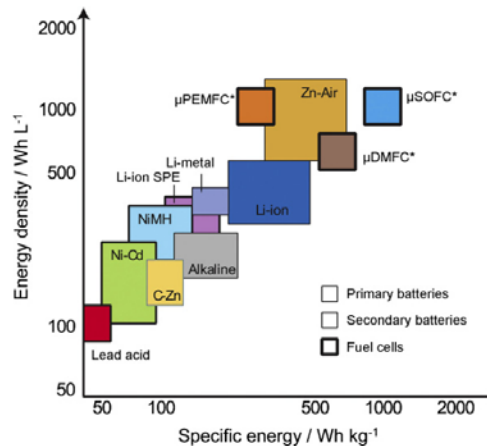


Photonics¹



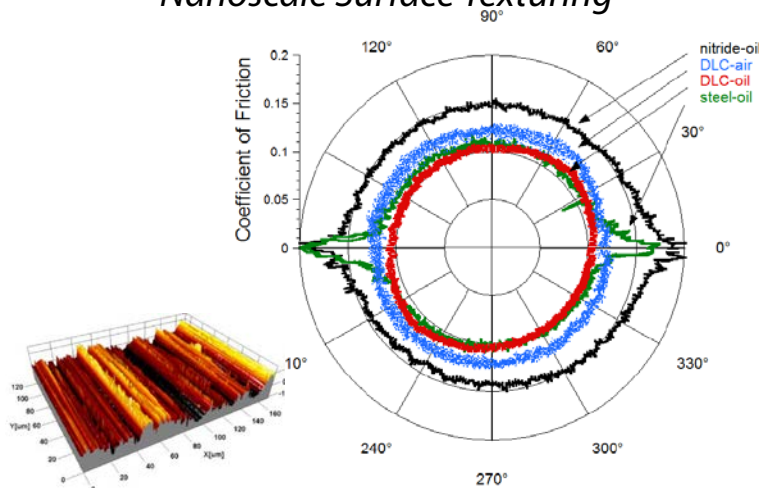
Nano-antenna array metasurfaces

Micro-SOFC²



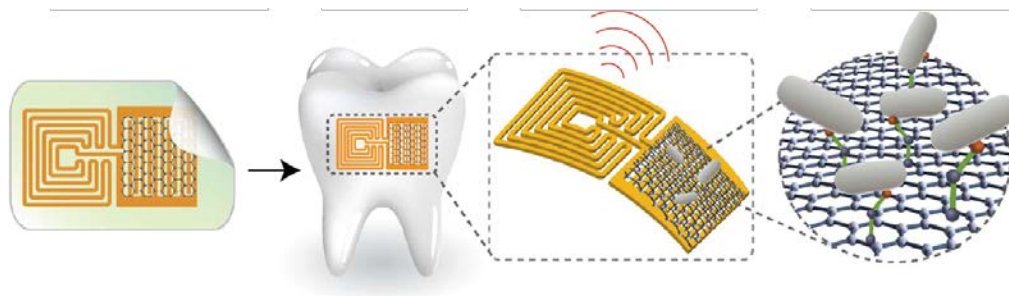
Electrolytic YSZ layers in micro-SOFC

Nanoscale Surface Texturing³



[1] A.V. Kildishev *et al.*, Science (2013)
 [2] J.H. Shim *et al.*, Chem. Mater. (2007)

Nano circuit printing and biological sensors⁴



[3] R. Erck *et al.*, Proc. ASME/STLE IJTC (2012)
 [4] M.S. Mannoor *et al.*, Nat. Comm. (2012)



- Nano-Tribological Printing is a versatile method for printing complex patterns with varying pattern height and shape
- It provides a novel additive printing technique capable of creating robust patterns without the need for chemical or thermal stimulus
- In-situ imaging during patterning provides real-time assessment of pattern quality
- Printed patterns show highly dense microstructure and mechanical properties nearly similar to corresponding bulk material values
- Nano-Tribological Printing can be scaled up with SPM arrays (e.g. IBM millipede)

Acknowledgements

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